

FORM PTO-1449		US Dept. of Commerce Patent and Trademark Office		ATTORNEY DOCKET NO.		SERIAL NO.			
INFORMATION DISCLOSURE STATEMENT (use several sheets if necessary)		521		TBA		jc986 U.S. PTO 09/929564 08/14/01			
		APPLICANT							
		Ying Ma, et al.							
		FILING DATE		GROUP					
		Herewith		TBA					
U.S. PATENT DOCUMENTS									
EXAMINER INITIAL		PATENT NUMBER	ISSUE DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE		
<i>[Signature]</i>	AA	5,527,423	6/18/1996	Neville, et al.					
<i>[Signature]</i>	AB	6,063,306	5/16/2000	Kaufman, et al.					
<i>[Signature]</i>	AC	5,676,587	10/14/1997	Landers					
<i>[Signature]</i>	AD	6,001,730	12/14/1999	Farkas, et al.					
<i>[Signature]</i>	AE	6,242,351	6/5/2001	Li, et al.					
<i>[Signature]</i>	AF	09/562,298	5/1/2000	Thomas H. Baum, et al.					
FOREIGN PATENT DOCUMENTS									
		DOCUMENT NUMBER	PUBLICATION DATE	COUNTRY	CLASS	SUBCLASSES	TRANSLATION YES NO		
							X (abstract only)		
<i>[Signature]</i>	AG	01/02134	11 Jan 2001	World					
OTHER DOCUMENTS (Including Author, Title, Journal-Date, Page Number, Etc.)									
<i>[Signature]</i>	AH	Jianfeng Luo, et al. "Integrated Model for Chemical-Mechanical Polishing Based on A Comprehensive Material Removal Model", Sixth International Conference on Chemical-Mechanical Polish (CMP) Planarization for ULSI Multilevel Interconnection (CMP-MIC), Santa Clara, CA USA March 8-9, 2001. ✓							
<i>[Signature]</i>	AI	Byron J. Palla, et al., "Stabilization of High Ionic Strength Slurries Using the Synergistic Effects of a Mixed Surfactant System", Journal of Colloid and Interface Science 223, 102-111 (2000). ✓							
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EXAMINER <i>[Signature]</i>					DATE CONSIDERED 6/16/03				
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.									

OK - Considered